

# INTERNATIONAL STANDARD

## NORME INTERNATIONALE

**Semiconductor devices – Non-destructive recognition criteria of defects in silicon carbide homoepitaxial wafer for power devices –  
Part 3: Test method for defects using photoluminescence**

**Dispositifs à semiconducteurs – Critères de reconnaissance non destructifs des défauts au sein d'une plaquette homoépitaxiale de carbone de silicium pour des dispositifs d'alimentation –  
Partie 3: Méthode d'essai pour les défauts à l'aide de la photoluminescence**





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IEC Central Office  
3, rue de Varembé  
CH-1211 Geneva 20  
Switzerland

Tel.: +41 22 919 02 11  
[info@iec.ch](mailto:info@iec.ch)  
[www.iec.ch](http://www.iec.ch)

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## SEMICONDUCTOR DEVICES – NON-DESTRUCTIVE RECOGNITION CRITERIA OF DEFECTS IN SILICON CARBIDE HOMOEPIТАXIAL WAFER FOR POWER DEVICES –

### Part 3: Test method for defects using photoluminescence

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The text of this International Standard is based on the following documents:

FDIS	Report on voting
47/2628/FDIS	47/2638/RVD

Full information on the voting for the approval of this International Standard can be found in the report on voting indicated in the above table.

This document has been drafted in accordance with the ISO/IEC Directives, Part 2.

A list of all parts in the IEC 63068 series, published under the general title *Semiconductor devices – Non-destructive recognition criteria of defects in silicon carbide homoepitaxial wafer for power devices*, can be found on the IEC website.

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## INTRODUCTION

Silicon carbide (SiC) is widely used as a semiconductor material for next-generation power semiconductor devices. SiC, as compared with silicon (Si), has superior physical properties such as a higher breakdown electric field, higher thermal conductivity, lower thermal generation rate, higher saturated electron drift velocity, and lower intrinsic carrier concentration. These attributes realize SiC-based power semiconductor devices with faster switching speeds, lower losses, higher blocking voltages, and higher temperature operation relative to standard Si-based power semiconductor devices.

SiC-based power semiconductor devices are not fully realized due to some issues including high costs, low yield, and low long-term reliability. In particular, one of the serious issues lies in the defects existing in SiC homoepitaxial wafers. Although efforts of decreasing defects in SiC homoepitaxial wafers are actively implemented, there are a number of defects in commercially available SiC homoepitaxial wafers. Therefore, it is indispensable to establish an international standard regarding the quality assessment of SiC homoepitaxial wafers.

The IEC 63068 series of standards is planned to comprise Part 1, Part 2, and Part 3, as detailed below. This document provides definitions and guidance in use of photoluminescence for detecting defects in commercially available silicon carbide (SiC) homoepitaxial wafers.

Part 1: Classification of defects

Part 2: Test method for defects using optical inspection

Part 3: Test method for defects using photoluminescence